

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Taiji EMA

Serial No.: 09/050,113

Group Art Unit: 2815

Filed: March 30, 1998

Examiner: C. WHITEHEAD JR.

For: SEMICONDUCTOR DEVICE AND METHOD FOR FABRICATING THE SAME

PRELIMINARY AMENDMENT

Assistant Commissioner for patents  
Washington, D.C. 20231

July 1, 1998

Sir:

This is a Preliminary Amendment for the above-captioned patent application.

Please amend the above-captioned patent application as follows:

IN THE CLAIMS:

Please amend claims 22 - 26 as follows:

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GROUP 2100

22. (Amended) [A semiconductor device] A method for fabricating the semiconductor device according to claim 20, wherein

in the contact hole forming step, the first insulating film is etched with a photoresist including an opening extended over the word lines, and the etching stopper film as a mask to form a plurality of the contact holes in the opening.

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